

POWER SUPPLY HARDENING FOR ION BEAM SYSTEMS

Abstract

An improved ion implantation system is provided by the present invention. The system includes at least one power supply for providing voltage to at least one electrode and, a switching system operatively coupled between the at least one power supply and the at least one electrode. The switching system decouples the at least one power supply and the at least one electrode at a predetermined threshold to mitigate overload of the at least one power supply.

Fig. 3